

Exhibit II

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Engineering & Materials: Electrical & Electronics

Engineering: Physical electronics

Physics: Solid state physics

Semiconductor

A solid crystalline material whose electrical conductivity is intermediate between that of a metal and an insulator. Semiconductors exhibit conduction properties that may be temperature-dependent, permitting their use as thermistors (temperature-dependent resistors), or voltage-dependent, as in varistors. By making suitable contacts to a semiconductor or by making the material suitably inhomogeneous, electrical rectification and amplification can be obtained. Semiconductor devices, rectifiers, and transistors have replaced vacuum tubes almost completely in low-power electronics, making it possible to save volume and power consumption by orders of magnitude. In the form of integrated circuits, they are vital for complicated systems. The optical properties of a semiconductor are important for the understanding and the application of the material. Photodiodes, photoconductive detectors of radiation, injection lasers, light-emitting diodes, solar-energy conversion cells, and so forth are examples of the wide variety of optoelectronic devices. See also: Integrated circuits; Laser; Light-emitting diode; Photodiode; Photoelectric devices; Semiconductor diode; Semiconductor rectifier; Thermistor; Transistor; Varistor

Conduction in Semiconductors

The electrical conductivity of semiconductors ranges from about 10^3 to 10^{-9} ohm⁻¹ cm⁻¹, as compared with a maximum conductivity of 10^7 for good conductors and a minimum conductivity of 10^{-17} ohm⁻¹ cm⁻¹ for good insulators. See also: Electric insulator; Electrical conductivity of metals

The electric current is usually due only to the motion of electrons, although under some conditions, such as very high temperatures, the motion of ions may be important. The basic distinction between conduction in metals and in semiconductors is made by considering the energy bands occupied by the conduction electrons. See also: Ionic crystals

A crystalline solid consists of a large number of atoms brought together into a regular array called a crystal lattice. The electrons of an atom can each have certain energies, so-called energy levels, as predicted by quantum theory. Because the atoms of the crystal are in close proximity, the electron orbits around different atoms overlap to some extent, and the electrons interact with each other; consequently the sharp, well-separated energy levels of the individual electrons actually spread out into energy bands. Each energy band is a quasicontinuous group of closely spaced energy levels. See also: Band theory of solids

At absolute zero temperature, the electrons occupy the lowest possible energy levels, with the restriction that at most two electrons with opposite spin may be in the same energy level. In semiconductors and insulators, there are just enough electrons to fill completely a number of energy bands, leaving the rest of the energy bands empty. The highest filled energy band is called the valence band. The next higher band, which is empty at absolute zero temperature, is

called the conduction band. The conduction band is separated from the valence band by an energy gap which is an important characteristic of the semiconductor. In metals, the highest energy band that is occupied by the electrons is only partially filled. This condition exists either because the number of electrons is not just right to fill an integral number of energy bands or because the highest occupied energy band overlaps the next higher band without an intervening energy gap. The electrons in a partially filled band may acquire a small amount of energy from an applied electric field by going to the higher levels in the same band. The electrons are accelerated in a direction opposite to the field and thereby constitute an electric current. In semiconductors and insulators, the electrons are found only in completely filled bands, at low temperatures. In order to increase the energy of the electrons, it is necessary to raise electrons from the valence band to the conduction band across the energy gap. The electric fields encountered are not large enough to accomplish this with appreciable probability. At sufficiently high temperatures, depending on the magnitude of the energy gap, a significant number of valence electrons gain enough energy thermally to be raised to the conduction band. These electrons in an unfilled band can easily participate in conduction. Furthermore, there is now a corresponding number of vacancies in the electron population of the valence band. These vacancies, or holes as they are called, have the effect of carriers of positive charge, by means of which the valence band makes a contribution to the conduction of the crystal. See also: Hole states in solids

The type of charge carrier, electron or hole, that is in largest concentration in a material is sometimes called the majority carrier and the type in smallest concentration the minority carrier. The majority carriers are primarily responsible for the conduction properties of the material. Although the minority carriers play a minor role in electrical conductivity, they can be important in rectification and transistor actions in a semiconductor.

Electron distribution

The probability f for an energy level E to be occupied by an electron is given by the Fermi-Dirac distribution function (1), where k

$$f = \left[1 + \exp \left(\frac{E - W}{kT} \right) \right]^{-1} \quad (1)$$

is the Boltzmann constant and T the absolute temperature. The parameter W is the Fermi energy level; an energy level at W has a probability of $1/2$ to be occupied by an electron. The Fermi level is determined by the distribution of energy levels and the total number of electrons. See also: Fermi-Dirac statistics

In a semiconductor, the number of conduction electrons is normally small compared with the number of energy levels in the conduction band, and the probability for any energy level to be occupied is small. Under such a condition, the concentration of conduction electrons is given by Eq. (2), where h is Planck's

$$N_n = \frac{2}{h^3} (2\pi m_n kT)^{3/2} \exp \left(\frac{W - E_c}{kT} \right) \quad (2)$$

constant, E_c is the lowest energy of the conduction band, and m_n is called the effective mass of conduction electrons. The effective mass is used in place of the actual mass to correct the coefficient in the equation and to bring the results in line with experimental observations. This correction is necessary because the theory leading to these equations is based upon electrons moving in a field free space, which is not the exact picture. The electrostatic Coulomb potential throughout the crystal is varying in a periodic manner, the variation being due to the electric

fields around the atomic centers. The concentration of holes in the valence band is given by Eq. (3) ,

$$N_p = \frac{2}{h^3} (2\pi m_p kT)^{3/2} \exp\left(\frac{E_v - W}{kT}\right) \quad (3)$$

where m_p is the effective mass of a hole and E_v is the highest energy of the valence band.

Mobility of carriers

The velocity acquired by charge carriers per unit strength of applied electric field is called the mobility of the carriers. The velocity in question is the so-called drift velocity in the direction of the force exerted on the carriers by the applied field. It is added to the random thermal velocity. In semiconductors the carrier mobility normally ranges from 10^2 to 10^5 $\text{cm}^2/(\text{s})(\text{V})$. A material's conductivity is the product of the charge, the mobility, and the carrier concentration.

Electrons in a perfectly periodic potential field can be accelerated freely. Impurities, physical defects in the structure, and thermal vibrations of the atoms disturb the periodicity of the potential field in the crystal, thereby scattering the moving carriers. It is the resistance produced by this scattering that limits the carriers to only a drift velocity under the steady force of an applied field.

Intrinsic semiconductors

A semiconductor in which the concentration of charge carriers is characteristic of the material itself rather than of the content of impurities and structural defects of the crystal is called an intrinsic semiconductor. Electrons in the conduction band and holes in the valence band are created by thermal excitation of electrons from the valence to the conduction band. Thus an intrinsic semiconductor has equal concentrations of electrons and holes. The intrinsic carrier concentration N_i is determined by Eq. (4) ,

$$N_i = \frac{2}{h^3} (2\pi kT)^{3/2} (m_n m_p)^{3/4} \exp\left(-\frac{E_g}{2kT}\right) \quad (4)$$

where E_g is the energy gap. The carrier concentration, and hence the conductivity, is very sensitive to temperature and depends strongly on the energy gap. The energy gap ranges from a fraction of 1 eV to several electronvolts. A material must have a large energy gap to be an insulator.

Extrinsic semiconductors

Typical semiconductor crystals such as germanium and silicon are formed by an ordered bonding of the individual atoms to form the crystal structure. The bonding is attributed to the valence electrons which pair up with valence electrons of adjacent atoms to form so-called shared pair or covalent bonds. These materials are all of the quadrivalent type; that is, each atom contains four valence electrons, all of which are used in forming the crystal bonds. See also: Crystal structure

Atoms having a valence of +3 or +5 can be added to a pure or intrinsic semiconductor material with the result that the +3 atoms will give rise to an unsatisfied bond with one of the valence electrons of the semiconductor atoms, and +5 atoms will result in an extra or free electron that

is not required in the bond structure. Electrically, the +3 impurities add holes and the +5 impurities add electrons. They are called acceptor and donor impurities, respectively. Typical valence +3 impurities used are boron, aluminum, indium, and gallium. Valence +5 impurities used are arsenic, antimony, and phosphorus.

Semiconductor material "doped" or "poisoned" by valence +3 acceptor impurities is termed *p*-type, whereas material doped by valence +5 donor material is termed *n*-type. The names are derived from the fact that the holes introduced are considered to carry positive charges and the electrons negative charges. The number of electrons in the energy bands of the crystal is increased by the presence of donor impurities and decreased by the presence of acceptor impurities. Let N be the concentration of electrons in the conduction band and let P be the hole concentration in the valence band. For a given semiconductor, the relation $NP = N_i^2$ holds, independent of the presence of impurities. The effect of donor impurities tends to make N larger than P , since the extra electrons given by the donors will be found in the conduction band even in the absence of any holes in the valence band. Acceptor impurities have the opposite effect, making P larger than N . See also: Acceptor atom; Donor atom

At sufficiently high temperatures, the intrinsic carrier concentration becomes so large that the effect of a fixed amount of impurity atoms in the crystal is comparatively small and the semiconductor becomes intrinsic. When the carrier concentration is predominantly determined by the impurity content, the conduction of the material is said to be extrinsic. There may be a range of temperature within which the impurity atoms in the material are practically all ionized; that is, they supply a maximum number of carriers. Within this temperature range, the so-called exhaustion range, the carrier concentration remains nearly constant. At sufficiently low temperatures, the electrons or holes that are supplied by the impurities become bound to the impurity atoms. The concentration of conduction carriers will then decrease rapidly with decreasing temperature, according to either $\exp(-E_i/kT)$ or $\exp(-E_i/2kT)$, where E_i is the ionization energy of the dominant impurity.

Physical defects in the crystal structure may have similar effects as donor or acceptor impurities. They can also give rise to extrinsic conductivity.

An isoelectronic impurity, that is, an atom which has the same number of valence electrons as the host atom, does not bind individual carriers as strongly as a donor or an acceptor impurity. However, it may show an appreciable binding for electron hole pairs, excitons, and thereby have important effects on the properties. An example is nitrogen substituting for phosphorus in gallium phosphide; the impurity affects the luminescence of the material.

Hall effect

Whether a given sample of semiconductor material is *n*- or *p*-type can be determined by observing the Hall effect. If an electric current is caused to flow through a sample of semiconductor material and a magnetic field is applied in a direction perpendicular to the current, the charge carriers are crowded to one side of the sample, giving rise to an electric field perpendicular to both the current and the magnetic field. This development of a transverse electric field is known as the Hall effect. The field is directed in one or the opposite direction depending on the sign of the charge of the carrier. See also: Hall effect

The magnitude of the Hall effect gives an estimate of the carrier concentration. The ratio of the transverse electric field strength to the product of the current and the magnetic field strength is called the Hall coefficient, and its magnitude is inversely proportional to the carrier concentration. The coefficient of proportionality involves a factor which depends on the energy distribution of the carriers and the way in which the carriers are scattered in their motion. However, the value of this factor normally does not differ from unity by more than a factor of 2.

The situation is more complicated when more than one type of carrier is important for the conduction. The Hall coefficient then depends on the concentrations of the various types of carriers and their relative mobilities.

The product of the Hall coefficient and the conductivity is proportional to the mobility of the carriers when one type of carrier is dominant. The proportionality involves the same factor which is contained in the relationship between the Hall coefficient and the carrier concentration. The value obtained by taking this factor to be unity is referred to as the Hall mobility.

Materials and Their Preparation

The group of chemical elements which are semiconductors includes germanium, silicon, gray (crystalline) tin, selenium, tellurium, and boron.

Elemental semiconductors

Germanium, silicon, and gray tin belong to group IV of the periodic table and have crystal structures similar to that of diamond. Germanium and silicon are two of the best-known semiconductors. They are used extensively in devices such as rectifiers and transistors. Gray tin is a form of tin which is stable below 13°C (55°F). White tin, which is stable at higher temperatures, is metallic. Gray tin has a small energy gap and a rather large intrinsic conductivity, about $5 \times 10^3 \text{ ohm}^{-1} \text{ cm}^{-1}$ at room temperature. The *n*-type and *p*-type gray tins can be obtained by adding aluminum and antimony, respectively.

Selenium and tellurium both have a similar structure, consisting of spiral chains located at the corners and centers of hexagons. The structure gives rise to anisotropy of the properties of single crystals; for example, the electrical resistivity of tellurium along the direction of the chains is about one-half the resistivity perpendicular to this direction. Selenium has been widely used in the manufacture of rectifiers and photocells.

Semiconducting compounds

A large number of compounds are known to be semiconductors. Copper(I) oxide (Cu_2O) and mercury(II) indium telluride (HgIn_2Te_4) are examples of binary and ternary compounds. The series zinc sulfide (ZnS), zinc selenide (ZnSe), and zinc telluride (ZnTe), and the series zinc selenide (ZnSe), cadmium selenide (CdSe), and mercury(II) selenide (HgSe) are examples of binary compounds consisting of a given element in combinations with various elements of another column in the periodic table. The series magnesium antimonide (Mg_2Sb_2), magnesium telluride (MgTe), and magnesium iodide (MgI_2) is an example of compounds formed by a given element with elements of various other columns in the periodic table. See also: Periodic table

A group of semiconducting compounds of the simple type AB consists of elements from columns symmetrically placed with respect to column IV of the periodic table. Indium antimonide (InSb), cadmium telluride (CdTe), and silver iodide (AgI) are examples of III-V, II-IV, and I-VI compounds, respectively. The various III-V compounds are being studied extensively, and many practical applications have been found for these materials. Some of these compounds have the highest carrier mobilities known for semiconductors. The compounds have zincblende crystal structure which is geometrically similar to the diamond structure possessed by the elemental semiconductors, germanium and silicon, of column IV, except that the four nearest neighbors of each atom are atoms of the other kind. The II-VI compounds, zinc sulfide (ZnS) and cadmium sulfide (CdS), are used in photoconductive devices. Zinc sulfide is also used as a luminescent material. See also: Luminescence; Photoconductivity

Binary compounds of the group lead sulfide (PbS), lead selenide (PbSe), and lead telluride (PbTe) are sensitive in photoconductivity and are used as detectors of infrared radiation. The compounds, bismuth telluride (Bi_2Te_3) and bismuth selenide (Bi_2Se_3), consisting of heavy atoms, are found to be good materials for thermocouples used for refrigeration or for conversion of heat to electrical energy. See also: Thermoelectricity

The metal oxides usually have large energy gaps. Thus pure oxides are usually insulators of high resistivity. However, it may be possible to introduce into some of the oxides impurities of low ionization energies and thus obtain relatively good extrinsic conduction. Copper(I) oxide (Cu_2O) was one of the first semiconductors used for rectifiers and photocells: extrinsic *p*-type conduction is obtained by producing an excess of oxygen over the stoichiometric composition, that is, the 2-to-1 ratio of copper atoms to oxygen atoms. A number of oxide semiconductors can be obtained by replacing some of the normal metal atoms with metal atoms of one more or less valency. The method is called controlled valence. An example of such a semiconductor is nickel oxide containing lithium.

Some compounds with rare-earth or transition-metal ions in their composition, such as EuTe and NiS_2 , are semiconductors with magnetic properties. Another interesting type of semiconductor is characterized by layered structures. The interaction within a layer is significantly stronger than that between layers. A number of semiconductors of this type are known, such as PbI_2 , GaSe, and various transition-metal dichalcogenides such as SnSe_2 and MoS_2 .

Preparation of materials

The properties of semiconductors are extremely sensitive to the presence of impurities. It is therefore desirable to start with the purest available materials and to introduce a controlled amount of the desired impurity. The zone-refining method is often used for further purification of obtainable materials. The floating zone technique can be used, if feasible, to prevent any contamination of molten material by contact with crucible. See also: Zone refining

For basic studies as well as for many practical applications, it is desirable to use single crystals. Various methods are used for growing crystals of different materials. For many semiconductors, including germanium, silicon, and the III-V compounds, the Czochralski method is commonly used. The method of condensation from the vapor phase is used to grow crystals of a number of semiconductors, for instance, selenium and zinc sulfide. For materials of high melting points, such as various metal oxides, the flame fusion or Vernonil method may be used. See also: Crystal growth

The introduction of impurities, or doping, can be accomplished by simply adding the desired quantity to the melt from which the crystal is grown. Normally, the impurity has a small segregation coefficient, which is the ratio of equilibrium concentrations in the solid and the liquid phases of the material. In order to obtain a desired impurity content in the crystal, the amount added to the melt must give an appropriately larger concentration in the liquid. When the amount to be added is very small, a preliminary ingot is often made with a larger content of the doping agent; a small slice of the ingot is then used to dope the next melt accurately. Impurities which have large diffusion constants in the material can be introduced directly by holding the solid material at an elevated temperature while this material is in contact with the doping agent in the solid or the vapor phase.

A doping technique, ion implantation, has been developed and used extensively. The impurity is introduced into a layer of semiconductor by causing a controlled dose of highly accelerated impurity ions to impinge on the semiconductor. See also: Ion implantation

An important subject of scientific and technological interest is amorphous semiconductors. In an amorphous substance the atomic arrangement has some short-range but no long-range order. The representative amorphous semiconductors are selenium, germanium, and silicon in their amorphous states, and arsenic and germanium chalcogenides, including such ternary systems as Ge-As-Te. Some amorphous semiconductors can be prepared by a suitable quenching procedure from the melt. Amorphous films can be obtained by vapor deposition.

Rectification in Semiconductors

In semiconductors, narrow layers can be produced which have abnormally high resistances. The resistance of such a layer is nonohmic; it may depend on the direction of current, thus giving rise to rectification. Rectification can also be obtained by putting a thin layer of semiconductor or insulator material between two conductors of different material.

Barrier layer

A narrow region in a semiconductor which has an abnormally high resistance is called a barrier layer. A barrier may exist at the contact of the semiconductor with another material, at a crystal boundary in the semiconductor, or at a free surface of the semiconductor. In the bulk of a semiconductor, even in a single crystal, barriers may be found as the result of a nonuniform distribution of impurities. The thickness of a barrier layer is small, usually 10^{-3} to 10^{-5} cm.

A barrier is usually associated with the existence of a space charge. In an intrinsic semiconductor, a region is electrically neutral if the concentration n of conduction electrons is equal to the concentration p of holes. Any deviation in the balance gives a space charge equal to $e(p - n)$, where e is the charge on an electron. In an extrinsic semiconductor, ionized donor atoms give a positive space charge and ionized acceptor atoms give a negative space charge. Let N_d and N_a be the concentrations of ionized donors and acceptors, respectively. The space charge is equal to $e(p - n + N_d - N_a)$.

A space charge is associated with a variation of potential. A drop in potential $-\Delta V$ increases the potential energy of an electron by $e\Delta V$; consequently every electronic energy level in the semiconductor is shifted by this amount. With a variation of potential, the electron concentration varies proportionately to $\exp(eV/kT)$ and the hole concentration varies as $\exp(-eV/kT)$. A space charge is obtained if the carriers, mainly the majority carriers, fail to balance the charge of the ionized impurities.

A conduction electron in a region where the potential is higher by ΔV must have an excess energy of $e\Delta V$ in order for it to have the minimum energy on reaching the low potential region. Electrons with less energy cannot pass over to the low potential region. Thus a potential variation presents a barrier to the flow of electrons from high to low potential regions. It also presents a barrier to the flow of holes from low to high potential regions.

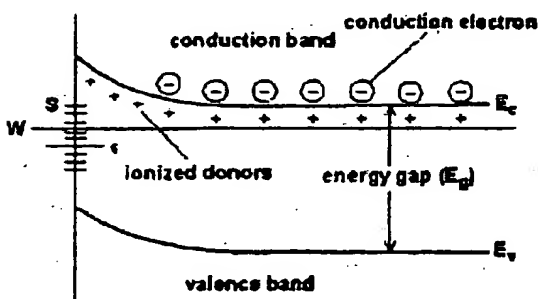
Surface barrier

A thin layer of space charge and a resulting variation of potential may be produced at the surface of a semiconductor by the presence of surface states. Electrons in the surface states are bound to the vicinity of the surface, and the energy levels of surface states may lie within the energy gap. Surface states may arise from the adsorption of foreign atoms. Even a clean surface may introduce states which do not exist in the bulk material, simply by virtue of being the boundary of the crystal.

The surface is electrically neutral when the surface states are filled with electrons up to a certain

energy level ϵ in the energy gap E_g , which is the energy difference between the bottom of the conduction band E_c and the top of the valence band E_v . If the Fermi level W in the bulk semiconductor lies higher in the energy gap, more surface states would be filled, giving the surface a negative charge. As a result the potential drops near the surface and the energy bands are raised for n -type material (Fig. 1). With the rise of the conduction band, the electron concentration is reduced and a positive space charge due to ionized donors is obtained. The amount of positive space charge is equal to the negative surface charge given by the electrons in the surface states between ϵ and the Fermi level.

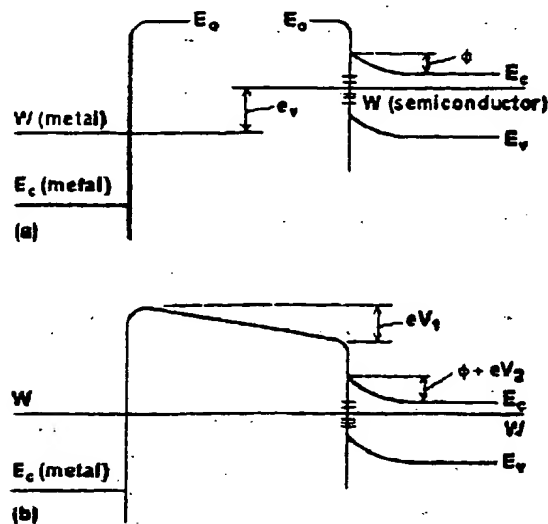
Fig. 1 Energy diagram of a surface barrier as employed in an n -type semiconductor.



Contact barrier

The difference between the potential energy E_0 of an electron outside a material and the Fermi level in the material is called the work function of the material. Figure 2 shows the energy diagram for a metal and a semiconductor, the work functions of which differ by eV . Upon connecting the two bodies electrically, charge is transferred between them so that the potential of the semiconductor is raised relative to that of the metal; that is, the electron energy levels in the semiconductor are lowered. Equilibrium is established when the Fermi level is the same in the two bodies. In this case, the metal is charged negatively and the semiconductor is charged positively. The negative charge on the metal is concentrated close to the surface, as is expected in good conductors. The positive charge on the semiconductor is divided between the increase of space charge in an extension of the barrier and the depopulation of some of the surface states. The charging of the semiconductor is brought about by a change of eV_2 in the barrier height ϕ . The sum of eV_2 and the potential energy variation eV_1 in the space between the two bodies is equal to the original difference eV between the work functions.

Fig. 2 Energy diagram for a metal (left) and an n -type semiconductor (right). E_0 is the potential energy of an electron outside the material, E_c is the energy at the bottom of the conduction band, and E_v is the energy at the top of the valence band. (a) Semiconductor and metal isolated. (b) Semiconductor and metal in electrical contact, $eV_1 + eV_2 = eV$.



With decreasing separation between the two bodies, the division of eV will be in favor of eV_2 . However, if there is a very large density of states, a small eV_2 gives a large surface charge on the semiconductor due to the depopulation of surface states.

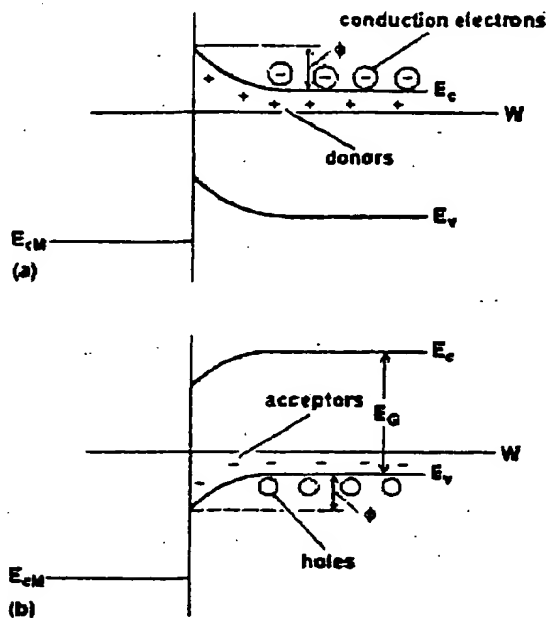
It is possible that eV_2 is limited to a small value even at the smallest separation, of the order of an interatomic distance in solids. In such cases, the barrier height remains nearly equal to the value ϕ of the free surface, irrespective of the body in contact. This situation has been found in germanium and silicon rectifiers. Before the explanation was given by J. Bardeen, who postulated the existence of surface states, it had been assumed that the height of a contact barrier was equal to the difference of the work functions.

The understanding and the application of metal-semiconductor contacts have been extended to various kinds of contacts, such as that between different semiconductors, heterojunctions, and metal oxide semiconductor (MOS) junctions.

Single-carrier theory

The phenomenon of rectification at a crystal barrier can be described according to the role played by the carriers. Where the conduction property of the rectifying barrier is determined primarily by the majority carriers, the single-carrier theory is employed. Such cases are likely to be found in semiconductors with large energy gaps, for instance, oxide semiconductors. Figure 3 shows the energy diagrams of metal-semiconductor contact rectifiers under conditions of equilibrium. The potential variation in the semiconductor is such as to reduce the majority carrier concentration near the contact. If the energy bands were to fall in the case of an n -type semiconductor or to rise in the case of a p -type semiconductor, the majority carrier concentration would be enhanced near the contact, and the contact would not present a large and rectifying resistance. It is clear that in the cases shown in Fig. 3, the minority carrier concentration increases near the contact. However, if the energy gap is large, the minority carrier concentration is normally very small, and the role of minority carriers may be still negligible even if the concentration is increased.

Fig. 3 Energy diagrams of a rectifying contact between a metal and a semiconductor: (a) n -type semiconductor; (b) p -type semiconductor.

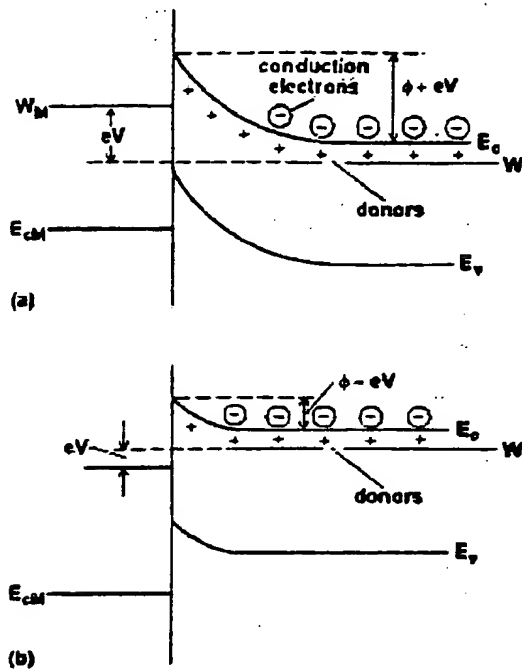


Under equilibrium conditions, the number of carriers passing from one body to the other is balanced by the number of carriers crossing the contact in the opposite direction, and there is no net current. The carriers crossing the contact in either direction must have sufficient energies to pass over the peak of the barrier. The situations under applied voltages are shown in Fig. 4 for the case of an *n*-type semiconductor. When the semiconductor is made positive, its energy bands are depressed and the height of the potential barrier is increased, as shown in Fig. 4a. Fewer electrons in the semiconductor will be able to cross over into the metal, whereas the flow of electrons across the contact from the metal side remains unchanged. Consequently, there is a net flow of electrons from the metal to the semiconductor. The flow of electrons from the metal side is the maximum net flow obtainable. With increasing voltage, the current saturates and the resistance becomes very high. Figure 4b shows the situation when the semiconductor is negative under the applied voltage. The energy bands in the semiconductor are raised. The flow of electrons from the semiconductor to the metal is increased, since electrons of lower energy are able to go over the peak of the barrier. The result is a net flow of electrons from the semiconductor to the metal. There is no limit to the flow in this case. In fact, the electron current increases faster than the applied voltage because there are increasingly more electrons at lower energies. The resistance decreases, therefore, with increasing voltage. The direction of current for which the resistance is low is called the forward direction, while the opposite is called the reverse or blocking direction. A general expression for the current can be written in the form of Eq. (5), where j is

$$j = enC \left(\exp \frac{-\phi}{kT} \right) \left[\exp \left(\frac{eV}{kT} \right) - 1 \right] \quad (5)$$

the current density, n is the carrier concentration in the bulk of the semiconductor, ϕ is the barrier height, and V is the applied voltage taken as positive in the forward direction. The factor C depends on the theory appropriate for the particular case.

Fig. 4 Energy diagrams of a rectifying contact between a metal and an *n*-type semiconductor under an applied voltage V . (a) Positive semiconductor. There is a net flow of electrons from metal to semiconductor. (b) Negative semiconductor. There is a net flow of electrons from semiconductor to metal.



Diffusion theory

When there is a variation of carrier concentration, a motion of the carriers is produced by diffusion in addition to the drift determined by the mobility and the electric field. The transport of carriers by diffusion is proportional to the carrier concentration gradient and the diffusion constant. The diffusion constant is related to the mobility, and both are determined by the scattering suffered by moving carriers. The average distance traveled by a carrier in its random thermal motion between collisions is called the mean free path. If barrier thickness is large compared to mean free path of carriers, motion of carriers in the barrier can be treated as drift and diffusion. This viewpoint is the basis of the diffusion theory of rectification. According to this theory, the factor C in Eq. (5) depends on the mobility and the electric field in the barrier.

Diode theory

When the barrier thickness is comparable to or smaller than the mean free path of the carriers, then the carriers cross the barrier without being scattered, much as in a vacuum tube diode.

According to this theory, the factor C in the rectifier equation is $v/4$, where v is the average thermal velocity of the carriers.

Tunneling theory

Instead of surmounting a potential barrier, carriers have a probability of penetrating through the barrier. The effect, called tunneling, becomes dominant if the barrier thickness is sufficiently small. This effect is important in many applications. See also: Tunneling in solids

Two-carrier theory

Often the conduction through a rectifying barrier depends on both electron and hole carriers. An important case is the pn junction between p - and n -sections of a semiconductor material. Also, in metal-semiconductor rectifiers, the barrier presents an obstacle for the flow of majority carriers but not for the flow of minority carriers, and the latter may become equally or more

important.

Rectification at pn junctions

A *pn* junction is the boundary between a *p*-type region and an *n*-type region of a semiconductor. When the impurity content varies, there is a variation of electron and hole concentrations. A variation of carrier concentrations is related to a shift of the energy bands relative to the constant Fermi level. This is brought about by a variation of the electrostatic potential which requires the existence of a space charge. If the impurity content changes greatly within a short distance, a large space charge is obtained within a narrow region. Such is the situation existing in a rectifying *pn* junction.

When a voltage is applied to make the *n*-region negative relative to the *p*-region, electrons flow from the *n*-region, where they are abundant, into the *p*-region. At the same time, holes flow from the *p*-region, where holes are abundant, into the *n*-region. The resistance is therefore relatively low. The direction of current in this case is forward. Clearly, the resistance will be high for current in the reverse direction.

With a current in the forward direction, electrons in the *n*-region and holes in the *p*-region flow toward the junction and there must be continuous hole-electron recombination in the neighborhood of the junction. The minority carrier concentration in each region is increased near the junction because of the influx of the carriers from the other region. This phenomenon is known as carrier injection. When there is a current in the reverse direction, there must be a continuous generation of holes and electrons in the neighborhood of the junction, from which electrons flow out into the *n*-region and holes flow out into the *p*-region. Thus current through a *pn* junction is controlled by the hole-electron recombination or generation in the vicinity of the junction.

The transistor consists of two closely spaced *pn* junctions in a semiconductor with an order *pn**p* or *n**pn*.

Contact rectification

If the height of a rectifying contact barrier is high, only a very small fraction of majority carriers can pass over the barrier. The fraction may be so small as to be comparable with the concentration of the minority carriers, provided the energy gap is not too large. The current due to the minority carriers becomes appreciable if the barrier height above the Fermi level approaches the energy difference between the Fermi level and the top of the valence band (Fig. 3).

The concentration of minority carriers is higher at the contact than in the interior of the semiconductor. With a sufficiently high barrier, it is possible to obtain at the contact a minority carrier concentration higher than that of the majority carriers. The small region where this condition occurs is called the inversion layer.

As in the case of a *pn* junction, a forward current produces injection of minority carriers. With the presence of an inversion layer, the injection can be so strong as to increase appreciably the conductivity in the vicinity of the contact. Ordinarily, contact rectifiers consist of a semiconductor in contact with a metal whisker. For large forward currents, the barrier resistance is small, and the resistance of the rectifier is determined by the spreading resistance of the semiconductor for a contact of small area. By increasing the conductivity in the vicinity of the contact where the spreading resistance is concentrated, carrier-injection may reduce considerably the forward resistance of the rectifier.

Surface electronics

The surface of a semiconductor plays an important role technologically, for example, in field-effect transistors and charge-coupled devices. Also, it presents an interesting case of two-dimensional systems where the electric field in the surface layer is strong enough to produce a potential wall which is narrower than the wavelengths of charge carriers. In such a case, the electronic energy levels are grouped into subbands, each of which corresponds to a quantized motion normal to the surface, with a continuum for motion parallel to the surface. Consequently, various properties cannot be trivially deduced from those of the bulk semiconductor. See also: Charge-coupled devices; Surface physics

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DOI 10.1036/1097-8542.614010

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